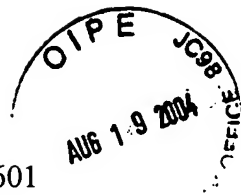


Docket No.: 50432-601



IFW

PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Application of	:	Customer Number: 20277
Minh Van NGO, et al.	:	Confirmation Number: 3500
Serial No.: 10/617,451	:	Group Art Unit: 2812
Filed: July 11, 2003	:	Examiner: W. Lindsay, Jr.
For: PECVD SILICON-RICH OXIDE LAYER FOR REDUCED UV CHARGING	:	

RESPONSE TO RESTRICTION REQUIREMENT

Mail Stop Restriction Requirement
Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

In the Office Action dated August 9, 2004, the Examiner imposed a Restriction Requirement pursuant to 35 U.S.C. §121, requiring election of either:

Group I. Claims 12 through 19 directed to a semiconductor device; or

Group II. Claims 1 through 11 directed to a method.

In response Applicants elect to prosecute device claims 12 through 19 (Group I).

Favorable consideration of device claims 12 through 19 is solicited.

Applicants also solicit rejoinder of non-elected method claims 1 through 11, upon the determination of an allowable device claim, pursuant to the provisions of MPEP§821.04.


To the extent necessary, a petition for an extension of time under 37 C.F.R. 1.136 is hereby made. Please charge any shortage in fees due in connection with the filing of this paper, including

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extension of time fees, to Deposit Account 500417 and please credit any excess fees to such deposit account.

Respectfully submitted,

MCDERMOTT WILL & EMERY LLP


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Date: August 19, 2004